

Consoommation et
Affaires commerciales Canada
Bureau des brevets
Ottawa, Canada
K1A 0C9

Consumer and
Corporate Affairs Canada
Patent Office

(11) (C)	1,325,582
(21)	608,246
(22)	1989/08/14
(45)	1993/12/28
(52)	148-2.8

(51) INVL-CL. 5 H01L-021/368

(19) (CA) CANADIAN PATENT (12)

(54) Process for Doping Crystals of Wide Band Gap
Semiconductors

(72) Neumark, Gertrude P. , U.S.A.

(73) Same as inventor

(30) (US) U.S.A. 232,405 1988/CB/15
(US) U.S.A. 234,802 1988/08/22

(57) 7 Claims

27632-1410/12686

1325582

BRUMBADGE, GRAVES, DONCHUE & RAYMOND
30 ROCKEFELLER PLAZA
NEW YORK, NEW YORK 10112

5 TO ALL WHOM IT MAY CONCERN:

Be it known that I, GERTRUDE P. NEUMARK, a
citizen of the United States, residing in Hartsdale,
County of Westchester, State of New York, whose post
office address is 153 Old Colony Road, Hartsdale, New York
10530, have invented an improvement in

A PROCESS FOR DOPING CRYSTALS OF WIDE
BAND GAP SEMICONDUCTORS

of which the following is a

SPECIFICATION

15

BACKGROUND OF THE INVENTION

This invention relates to the preparation of
crystals of wide band gap semiconductors for use in
electronic devices.

As is known, crystals of semiconductors are of
20 great interest in the manufacture of sophisticated
electronic devices. The useful properties of
semiconductive crystals depend not only on the particular
semiconductor that forms the crystal but also importantly
on the trace amounts of donor or acceptor dopants that are
25 incorporated in the crystal lattice. These dopants
contribute the hole and electron charge carriers that are
responsible for the useful electronic properties of the
crystals.



27632-1418/12686

1325582

with many potentially useful semiconductive crystals, particularly those in which the host material is a wide band-gap semiconductor (a band gap of at least 1.4 electron volts). Such as zinc selenide, it has been difficult to incorporate into the crystal lattice in reproducible fashion adequate amounts of both types of dopant to provide good p-n junctions, i.e., both n-type and p-type conductivity. As a consequence, it has not been practical to use such semiconductors widely in devices where bipolar conductivity is important.

In particular, although n-type zinc selenide has been available which conducts "well" (defined as having a resistivity equal to or less than 10^3 ohm-centimeter), this has not been the case with p-type zinc selenide. The standard practice for preparing "well-conducting" n-type zinc selenide involves the extraction of impurities, such as copper, by annealing. Such annealing is known to extract copper that is accidentally introduced during the preparation of bulk material.

More recently n-type zinc selenide has been prepared using low temperature growth methods, such as metal-organo-chemical vapor deposition (MOCVD) and molecular beam epitaxy (MBE) with selective incorporation of appropriate dopants.

However, with respect to p-type zinc selenide, it has been difficult to obtain "well-conducting" material reliably in reproducible fashion. There have been recent claims that such material has been realized by the introduction of Li_3N . Others have claimed to have obtained it by the introduction of gallium, indium or

1325582

thallium by heat treatment and diffusion. However, the understanding of these techniques has been poor with the result that there is little confidence in applying these techniques to commercial products.

5 There is needed a better-understood technique, amenable to good control, for doping hard-to-dope wide band gap semiconductors, such as zinc selenide, zinc sulphide, cadmium sulphide, cadmium selenide, zinc telluride and diamond.

10

SUMMARY OF THE INVENTION

I believe that energy and solubility considerations form the basic difficulty in incorporating particular dopants into crystals of the kind under discussion. Such considerations predict a strong tendency 15 for compensation between donors and acceptors in wide band gap materials. Accordingly, the achievement of adequate conductivity will require "non-equilibrium impurity incorporation". This term means the incorporation of a dopant (impurity) in excess of its equilibrium solubility 20 at a particular temperature and concentration of compensating species. As is also known, the solubility of a donor or an acceptor at a given temperature will increase with an increase in concentration of compensating species so that, in effect, compensation increases the 25 solubility of a dopant.

Moreover to be of practical use, such non-equilibrium incorporation needs to persist over reasonable time scales at operating temperatures, so that the mobility of the desired dopant needs be low enough that

27632-1418/12656

1325582

the dopant remains locked in the crystal lattice after the initial non-equilibrium incorporation.

Various techniques are feasible for achieving non-equilibrium incorporation. The simplest is to introduce the desired dopant species at a temperature where its mobility and solubility is high, with subsequent fast quenching to a lower temperature where the mobility is low, to lock the dopant in the lattice. A variant of this has been suggested in which the preferred site of an amphoteric dopant can be a function of temperature. However, these techniques for achieving a non-equilibrium concentration have been of limited usefulness, particularly with respect to wide-band gap materials that are difficult to make "well-conducting."

A feature of the present invention is an approach to achieving a non-equilibrium concentration that uses consciously, with optimum parameters, phenomena that may have been accidentally involved in the past. In my new technique, a desired primary dopant species is introduced into the semiconductor of interest together with a concentration, preferably nearly the same, of a suitable secondary compensating species, advantageously one more mobile at lower temperatures. The compensating species acts to increase the solubility of the desired dopant so that the concentration introduced of the desired dopant may be larger than the equilibrium value in the absence of the compensating species. Subsequently, in a disciplined fashion, the more mobile compensating species is preferentially removed. Introduction of a chosen mobile compensating species, of a concentration closely

1325582

matching that of the desired dopant, will prevent or reduce the incorporation of other, possibly less mobile compensating species. In this case, after the removal of the selected mobile compensating species, the dopant remaining in the host crystal will be predominantly only the desired dopant whereby the material may be of high conductivity of the type imparted by the desired dopant.

In an illustrative example of a process, in accordance with my inventions, a layer of zinc selenide is 10 doped p-type with nitrogen by liquid phase epitaxial (LPE) growth from a lithium-rich melt. The doping with nitrogen may be achieved by using ammonia (NH_3) essentially in the manner described in a paper entitled "Ionization energy of the shallow nitrogen acceptor in zinc selenide" published 15 in Physical Review B, Vol. 27, Number 4, 15 February 1983, pps. 2419-2428. In the resulting layer, nitrogen is substituted in selenium sites as an acceptor, and lithium is incorporated in interstitial sites where it acts as a donor. Subsequent to its growth, the layer is heated to a 20 temperature of about 900°C in zinc vapor together with indium, gallium or thallium vapor. This heating tends to getter the faster diffusing lithium selectively from the layer whereby it is left doped primarily by nitrogen and so is of high conductivity p-type.

If a p-n junction is to be formed, an n-type zinc selenide crystal is used as the substrate in the LPE process in which the lithium-nitrogen epitaxial layer is grown. Advantageously the crystal used as the substrate is n-type by the inclusion, as the predominant dopant, of 25 a donor, such as iodine, that diffuses only slowly in the

1325582

27632-1418/12686

zinc selenide, so that little of it is lost during the lithium gettering step.

Additionally, hydrogen can be introduced simultaneously with the desired primary dopant in substantially equivalent amounts such that the concentration of the primary dopant in the zinc selenide is in excess of the solubility of the primary dopant alone to produce either n-type or p-type material. Hydrogen may act as a donor impurity to compensate p-type dopants, or act as an acceptor impurity to compensate n-type dopants. In either case, the effective solubility of the desired dopant will be increased, and after preferential removal of the more mobile hydrogen, the resistivity of the semiconductor bulk will be lower than that which can be achieved with introduction of the desired dopant alone.

DESCRIPTION OF THE DRAWING

The invention will be described in conjunction with the accompanying drawing that shows a p-n diode of Zn Se made in accordance with an illustrative embodiment of the invention.

1325582

DETAILED DESCRIPTION OF THE INVENTION

A p-n junction zinc selenide diode 10 including layers 12 and 14, suitable for use as a light-emitting diode, shown in the drawing, is prepared as follows.

5 There is first prepared the n-type slice 12 of zinc selenide in known fashion, for example, as described in a paper entitled "p-n junction zinc sulfo-selenide and zinc selenide light-emitting diodes" Applied Physics Letters, Vol. 27 No. 2, 15 July 1975 pp. 74-77. This 10 involves preparing a single crystal boule of n-type zinc selenide by an iodine transport technique, cutting a slice parallel to the (111) plane, and annealing the slice in molten zinc. The resulting material is made to have a resistivity of the order of 0.1 ohm-cm., corresponding to 15 an iodine concentration of between 10^{17} and 10^{18} per cc³. The slice desirably is about 1 mm. thick and 0.5 cm radius.

Thereafter, there is grown on one surface of the n-type slice 12, an epitaxial p-type layer 14, typically 20 between 5 and 10 microns thick, although even thinner layers can be used. This layer advantageously is grown by LPE to include both lithium and nitrogen in appropriate amounts in the manner described previously with reference to the Physical Review B paper. The amounts added are 25 best determined experimentally but should be adequate to provide, in the epitaxial layer grown, substantially equal concentrations of lithium and nitrogen, advantageously in the range between 10^{17} and 10^{18} per cc³. As long as the amounts of each in the melt are approximately equal, 30 because of strong compensating effects in such wide band

27632-1418/12686

1325582

gap crystals, substantially equal amounts of the two dopants will be introduced into the crystal. Because the presence of the lithium increases the effective solubility of the nitrogen, there can be introduced into the zinc selenide a normally non-equilibrium concentration, as previously discussed.

Then, in known fashion, the lithium is preferentially removed from the epitaxial layer. This is feasible because of the much lower mobility of nitrogen and iodine in zinc selenide in this temperature range. This results a p-type epitaxial layer with a nitrogen concentration of about 10^{17} per cc^3 . A suitable procedure is to heat the slice in the range of between 600°C-1000°C in zinc vapor together with either indium, gallium, or thallium as suggested in a paper entitled "The variation of residual impurities in Zn Se crystals used in light-emitting diodes fabrications", J. Appl. Phys. 53(2) February 1982, pgs. 1248-1250.

To complete the diode, a thin layer 16 of gold is deposited over the p-type layer to serve as one of the two electrodes of the diode. A dot 18 of indium is deposited over the bottom surface of the slice to serve as the other electrode of the diode. This leaves a considerable portion of the bottom surface free for the exit of the emitted light excited when an appropriate voltage is applied between the two electrodes. Such a diode emits blue light of about 460 nm wavelength.

Of course, other electrode configurations are possible, including ring-shaped electrodes, to facilitate the exit of the emitted light.

1325582

Additionally, the principles of the invention are applicable to the preparation of devices using wide band gap semiconductors other than zinc selenide.

A light-emitting p-n junction diode can be formed in zinc telluride in accordance with an alternative embodiment of the invention as follows.

A p-type crystal of ZnTe was grown from a Te rich solution by a Bridgman technique, as discussed in a paper entitled "SEM and Photoluminescence Study of Li Segregation in Annealed Zinc Telluride" published in Solid State Communications Vol. 29, pp. 35-38, Pergamon Press Ltd. 1979.

Then in known fashion, using metal-organic-chemical vapor deposition (MOCVD), an n-type epitaxial layer is grown on the top surface of the slice. In this case, the epitaxial layer is doped with chlorine as the primary dopant and lithium as the compensating or secondary dopant. Chlorine is a donor in zinc telluride at a tellurium substitutional site while lithium acts as an acceptor on a zinc substitutional site. Moreover, because of its larger ionic size, chlorine will be less mobile than will the lithium.

As before, the presence of the lithium will permit the introduction into the epitaxial layer of a higher concentration of the chlorine than normally possible, as discussed above, by increasing its effective solubility. Again, the amounts of each introduced into the epitaxial layer are made to be about equal.

Then, the zinc telluride slice is heated in a zinc atmosphere to remove the more mobile lithium

1325582

preferentially as, for example, is reported in a paper entitled "SEM and Photoluminescence Study of Li Segregation in Annealed Zinc Telluride", Solid State Communications, Vol. 29, pp. 35-38, Pergamon Press Ltd.

5 1979. Accordingly, chlorine becomes the predominant dopant in the epitaxial layer, whereby it becomes n-type. As before appropriate electrodes are provided to the opposite surfaces of the slice to form the diode.

In an alternative embodiment of the invention, 10 hydrogen is utilized as a secondary compensating dopant and is simultaneously diffused into the semiconductor with the desired primary dopant at an appropriate temperature. Hydrogen is also amphoteric in that it can be either a compensating donor or a compensating acceptor. A more 15 extensive discussion can be found in Pearson, S.J. et al., Appl. Phys. A 43, 153 (1987); and Johnson, N.M., et al al., Phys. Rev. Lett. 56, 769 (1986); Acceptors in CdTe have been neutralized with the introduction of hydrogen at about 350°C as further discussed in Boudoukha, A., et 20 al., J. Cryst. Growth 72, 226 (1985). Hydrogen will also act as a donor when introduced into ZnO at about 500-700°C as more fully discussed in Thomas, P.G., et al., J. Chem. Phys. 25, 1135 (1956).

Introducing hydrogen as a compensating dopant 25 together with the desired dopant increases the solubility of the desired dopant to be greater than if introduced alone. Subsequently, the hydrogen is preferentially removed and a semiconductor having much reduced compensation of the desired dopant and therefore much 30 lower resistivity is achieved. This alternative

1325582

embodiment can yield acceptably low resistivity p-type
CdS, CdSe, ZnS, and ZnSe, in addition to other wide band-
gap semiconductors which have a tendency to incorporate
donor compensators. Moreover, the same techniques may also
5 be used to produce acceptably low resistivity n-type
diamond and ZnTe, as well as other semiconductors which
have a tendency to incorporate acceptor compensators.

A first method of introducing hydrogen as a
secondary compensating species and the desired primary dopant
10 simultaneously into the crystal structure is via the joint

1325582

diffusion technique. Some dopants will diffuse at fairly low temperatures. For a review of diffusion rates, see Casey, Jr., H.C., et al., "Point Defects in Solids," Crawford, Jr., J.H. et al., Eds., Vol. 2, p. 163 (Plenum Press, N.Y. 1975). Accordingly, a wide range of conditions and temperatures are available for the simultaneous introduction of B and a primary dopant by joint diffusion.

Hydrogen and the desired primary dopant can also be introduced simultaneously during crystal growth. One requirement is that the growth temperature be sufficiently low in order to retain hydrogen in the semiconductor. Therefore, a temperature of approximately 700°C or below is desirable. Yet another technique of simultaneous hydrogen and dopant introduction is to use known ion implantation techniques.

As an example, p-type zinc selenide can be produced by conventional methods at usual high temperatures, to wit, 400°C or above. P-type zinc selenide may typically have sodium at the Zn substitutional site and/or nitrogen at the Se substitutional site. Hydrogen is simultaneously introduced with the desired primary acceptor dopant and, under these circumstances, acts like a donor impurity which effectively compensates the simultaneously introduced acceptor impurity and increases the solubility of the acceptor impurity. Typically, p-type zinc selenide tends to become heavily compensated by donors such as Group I metals going to the interstitial sites. Compensation also occurs if contaminating donors are unintentionally introduced into the zinc selenide substrate. Because hydrogen is made available in a relatively high concentration, it will act as a

1325582

compensating donor and significantly limit the presence of contaminating donors. Once the hydrogen is preferentially removed, p-type zinc selenide having suitably low compensation and consequently, suitably low resistivity, will remain.

Several methods are known for selectively removing the compensating hydrogen while allowing the desired acceptor or donor impurity to remain in the semiconductor. For example, the material can be heated to a temperature which is sufficient to cause relatively rapid out-diffusion of hydrogen from the material as compared to the rate of out-diffusion of the primary dopant at the same temperature. Temperatures between about 100 to 500°C and, more preferably, between about 150 to 450°C are generally effective. The actual preferred temperature depends on many factors including the specific primary dopant species used. Due to the high mobility of hydrogen, it will diffuse out while allowing the less mobile primary dopant to remain in the semiconductor. A temperature of approximately 250°C has been shown to be effective for this procedure.

Other known methods for extracting the hydrogen may be used. For example, a gettering process may be used in which the semiconductor, such as p-type zinc selenide, would be heated in the presence of a metal which has an affinity for hydrogen. In another known method, the hydrogen is removed through electric field induced hydrogen drift. Any method which would remove the hydrogen without appreciably removing the desired dopant(s) may be used in accordance with the invention.

Certain semiconductor materials have compensation problems when n-type dopants are introduced. These problems may also be alleviated by the method of this invention. For

1325582

example, it has not been heretofore practicable to produce high conductivity n-type ZnTe having a resistivity below 100 ohm-cm. To produce such high conductivity n-type ZnTe, hydrogen is introduced simultaneously with an appropriate desired donor dopant, such as chlorine. The semiconductor is allowed to cool, and the hydrogen is then extracted by any of the aforementioned methods, at a much lower temperature than the temperature at which the hydrogen and desired donor dopant was introduced. The resulting n-type ZnTe will have substantially lower compensation and correspondingly lower resistivity.

It should be evident that the basic principles described can be extended to various other systems of wide band gap materials and should be of special interest to materials that are normally difficult to dope adequately.

Basically, as described, by choosing an appropriate compensating pair of primary and secondary dopants, the amount of primary dopant introduced into a crystal may be larger than the solubility of the primary dopant in the crystal if introduced alone. Thereafter by the removal preferentially of the secondary dopant, typically by taking advantage of its higher mobility in the crystal, the crystal is left with a higher, non-equilibrium concentration of the primary dopant. Copper and gold are other examples of likely choices for use as the secondary dopant.

It should also be apparent that the invention should make feasible the formation of various other forms of electronic devices, such as transistors and injection lasers.

1325582

27632-1418/12686

Additionally, while there have been described embodiments using LPE and MOCVD for forming layers including compensating pairs of primary and secondary dopants, other techniques are feasible including molecular beam epitaxy (MBE).

27632-1418/12686

1325582

I. CLAIM:

1. A process for the non-equilibrium incorporation of a dopant into a crystal of a wide band gap semiconductor comprising the steps of treating the crystal in the presence of first and second compensating dopants of different mobilities for introducing substantially equal amounts of the two dopants into at least a portion of the crystal such that the concentration of the less mobile of the two dopants in said portion of the crystal is in excess of the solubility of the less mobile dopant therein in the absence of the more mobile of the two dopants, and then preferentially removing therefrom the more mobile of the two dopants whereby there is left a non-equilibrium concentration of the less mobile dopant in said portion of the crystal.

2. The process of claim 1 in which the semiconductor is zinc selenide and the more mobile dopant is lithium and the less mobile dopant is nitrogen.

3. The process of claim 1 in which the semiconductor is zinc selenide and the more mobile dopant is hydrogen and the less mobile dopant is nitrogen.

4. The process of claim 1 in which the semiconductor is zinc telluride and the more mobile dopant is lithium and the less mobile dopant is chlorine.

1325582

5. The process of claim 1 in which the semiconductor is zinc telluride and the more mobile dopant is hydrogen and the less mobile dopant is chlorine.

6. The process of claim 1 in which the more mobile dopant can move via interstitial sites and the less mobile dopant is at a substitutional sites in the crystal.

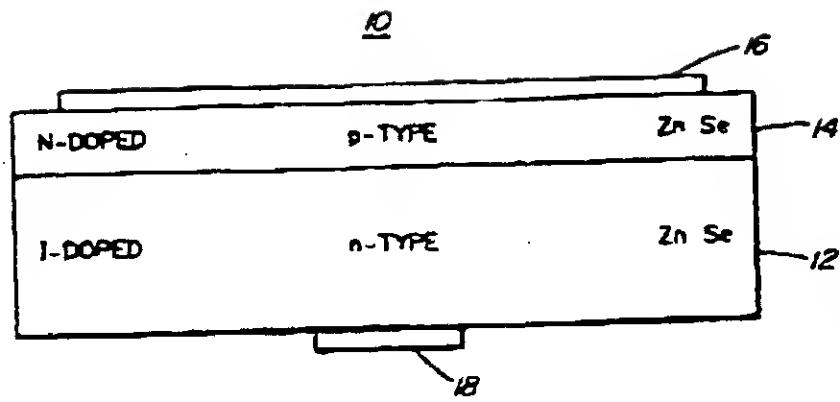
7. The process of forming a p-n junction diode in a crystal of a wide band gap semiconductor comprising the steps of

10 preparing a crystal of the semiconductor of one conductivity type and growing on a surface of the crystal an epitaxial layer that includes a compensating pair of primary and secondary dopants in substantially equal amounts, such that the concentration of the primary dopant in the layer is in excess of the solubility of the primary dopant in the layer in the absence of the secondary dopant, where the primary dopant is characteristic of the conductivity type opposite that of said crystal and is less mobile than the secondary dopant, and

15 20 removing selectively the secondary dopant from the layer to leave it of the opposite conductivity type, where the dopant remaining in the layer is predominantly the primary dopant in a non-equilibrium concentration.

68

1325582



G. B. Smith & Haldane

